



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Wen-Ben CHOU et al.

Application No. 09/998,858

Filed: October 31, 2001

For: METHOD AND APPARATUS
FOR NITRIDE SPACER ETCH
PROCESS IMPLEMENTING -
IN SITU INTERFEROMETRY
ENDPOINT DETECTION AND
NON-INTERFEROMETRY
ENDPOINT MONITORING

Docket No. LAM2P295

Examiner: Chen, Kin Chan

Group Art Unit: 1765

Date: July 1, 2004

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450 on July 1, 2004.

Signed:

Courtney F. Yadegar

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Dear Sir:

This is in response to the Office Action mailed on April 1, 2004. Please enter the following amendments and remarks in the above-identified patent application:

Amendments to the claims are reflected in the Listing of Claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 11 of this paper.

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